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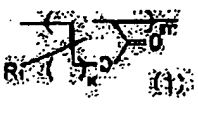
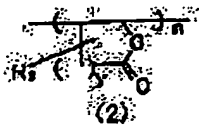
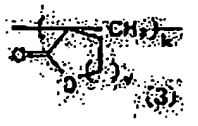
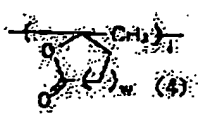
(54) RESIST COMPOSITION COMPRISING PHOTOSENSITIVE POLYMER CONTAINING LACTONE IN BACKBONE

(57)Abstract:
PROBLEM TO BE SOLVED: To provide a resist composition comprising a photosensitive polymer containing a lactone in the backbone.
SOLUTION: The photosensitive polymer constituting the resist composition contains at least one selected from repeating units of formulae (1)–(4) (where R1 and R2 are each H, alkyl, hydroxyalkyl, alkyloxy, carbonyl or ester and (x), (y), (v) and (w) are each an integer of 1–6).









LEGAL STATUS

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